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# **Single-Nanowire Photoelectrochemistry**

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Photoelectrochemistry<sup>1-3</sup> is one of several promising approaches<sup>4-5</sup> to realize efficient solarto-fuel conversion. Recent work has shown that photoelectrodes made of semiconductor nano/microwire arrays can have better photoelectrochemical (PEC) performance<sup>6-8</sup> than their planar counterparts because of their unique properties, such as high surface area<sup>9-11</sup>. Although much effort has been focused on studying wire arrays, inhomogeneity in the geometry, doping, defects and catalyst loading present in such arrays can obscure the link between these properties and the wires' PEC performance; correlating the performance with the specific properties of individual wire is difficult because of ensemble averaging. Here, we show that a single-nanowire-based photoelectrode platform can be used to reliably probe the current-voltage (I-V) characteristics of individual nanowires. We found that the photovoltage output of ensemble array samples can be limited by poorly performing individual wires, which highlights the importance of improving the nanowire homogeneity within an array. Furthermore, this platform allows the flux of photogenerated electrons to be quantified as a function of the lengths and diameters of individual nanowires, and the flux over the entire nanowire surface (7-30 electrons/ (nm<sup>2</sup>·s)) is found to be significantly reduced as compared to that of a planar analogue (~1,200 electrons/ (nm<sup>2</sup>·s)). Such characterization of the photo-generated carrier flux at the semiconductor/electrolyte interface is essential for designing nanowire photoelectrodes that match the activity of their loaded electrocatalysts.

Devices composed of single nanowires have previously been used in electronics<sup>12</sup>, bio-probing<sup>13</sup>, photovoltaics<sup>14, 15</sup>, thermoelectrics<sup>16</sup> and electrochemistry<sup>17</sup>. In this work we developed a well-

controlled device of single-semiconductor-nanowire (Fig. 1a) for photoelectrochemistry, which is capable of detecting solar-powered proton reduction with pico-ampere (pA) sensitivity. As a model system, silicon  $(Si)^{18-21}$  and platinum  $(Pt)^{22}$  are selected as the light-absorbing semiconductor and the proton-reduction electrocatalyst respectively. Si nanowires were grown epitaxially on the pre-patterned, degenerately-doped Si <111> device layer of a silicon-oninsulator (SOI) substrate, as shown in the scanning electron microscope (SEM) image (Fig. 1b). With an oxide layer underneath, the patterned Si electrodes are electrically isolated from each other, enabling the characterization of each nanowire individually. Moreover, the VLS growth allowed control over the nanowire's dimensions<sup>23</sup>, which facilitated studying the effects of the nanowire's geometry. In this work, the as-grown single Si nanowires were 8-20 µm long and 500-800 nm in diameter. The post-growth fabrication process yielded nanowires with two types of doping profiles (Fig. 2a). In one case, the as-grown Si nanowires were doped into *p*-type only. In the second case, after the *p*-type doping, an  $n^+$  shell was added to yield an  $n^+p$  buried junction in each single nanowire. For both types of devices, Pt nanoparticles were deposited electrolessly<sup>22</sup> onto the exposed nanowire (Supplementary Fig. 2, 3) after a protective polymer coating was added to the base of the wire. Additionally, a specialized PEC measurement setup was developed (Fig. 2b) for high-sensitivity electrochemical characterization coupled with simulated sunlight. This unique measurement platform can be further applied to other lightdriven redox reactions that require high sensitivity.

These aforementioned techniques provide us with a nanowire photoelectrode platform that is individually addressable and enable the first observation of single-nanowire photoelectrochemistry. The photocurrents of devices were characterized with pA sensitivity (Fig. 3a). In the dark, devices show negligible current (|I| < 1 pA). The slightly increased current at potentials negative of 0 V *vs*. the reversible hydrogen electrode (RHE) implies a proton-reduction reaction catalyzed by the loaded Pt nanoparticles (Supplementary Fig. 5). Under one-sun illumination (100 mW/cm<sup>2</sup>, AM 1.5G), a significant photoresponse was observed with the photocurrent reaching a plateau under negative bias, indicative of a light-activated process limited by the number of incident photons. Such PEC behavior is consistent with that of the reported ensemble systems<sup>18, 19</sup>, confirming the observation of PEC phenomena at the single-nanowire level. Additionally, the performance of the device was consistent for multiple scan cycles (Fig. 3b).

The photovoltage distribution statistics of the single-nanowire devices was analyzed next. For Si photocathodes, a previous study on ensemble systems proposed that the  $n^+p$  buried junction increases the degree of band bending at the interface and consequently leads to a 250-350 mV improvement in photovoltage<sup>18</sup>. This concept was also implemented in our single-nanowire photoelectrodes (Supplementary Scheme 1). The onset potentials and standard deviations of *p*-Si and  $n^+p$ -Si devices are  $280\pm110$  mV and  $530\pm120$  mV vs. RHE, respectively (Fig. 3c). The ~250 mV difference between the average onset potentials demonstrates that the single-nanowire photoelectrode's doping profile and photovoltage can be reproducibly modulated. In addition, for devices that underwent the same growth and doping process, the broad photovoltage distribution implies individual variance among single nanowires. To investigate the impact of such variance, we carried out PEC measurements on ensemble nanowire arrays (Supplementary Fig. 6), in which many individual nanowires are connected in parallel. It was found that the  $V_{oc}$  of the array device is comparable with that of the single nanowire with the lowest photovoltage output

(Supplementary Fig. 7), and this observation applied to both *p*-Si and  $n^+p$ -Si devices (Supplementary Fig. 8, Table 1). These results suggest that the photovoltage of the ensemble array photoelectrode is largely affected by the worst-performing individual nanowire, and this conclusion is further supported by our calculation based on an equivalent circuit model (Supplementary Fig. 9). Since the single nanowires and the nanowire arrays studied in this work have similar physical dimensions and go through the same doping process, such observed individual variance should be related to the heterogeneity of the material quality introduced during either the VLS growth<sup>24, 25</sup> or the fabrication process, or both. As a result, our report emphasizes the importance of controlling material quality not only in the averaged value but also the sample homogeneity, in order to produce efficient nanowire-based solar-to-fuel devices.

Owing to the high-sensitivity photocurrent measurement and the well-defined geometry of a single nanowire, the photo-generated electron flux through the nanowire's entire surface  $(Flux_{wire})$  was quantified. Because of the nanowire's large surface area,  $Flux_{wire}$  was much reduced compared to a planar analogue. In order to quantitatively evaluate how the large surface area functions to dilute the electron flux, the roughness factor of a single nanowire ( $\gamma_{rough}$ ) is introduced in equation (1). Here the nanowire is considered as a cylinder whose length and diameter are *L* and *D*, respectively.

$$\gamma_{rough} = \frac{\text{actual surface area of a single nanowire}}{\text{cross section area of a single nanowire}} = \frac{4L}{D} + 1$$
(1)

Subsequently, as shown in equation (2),  $Flux_{wire}$  can be correlated with  $Flux_{geo}$ , which is the photo-generated electron flux normalized to the geometric cross-sectional area.

$$Flux_{wire} = \frac{Flux_{geo}}{\gamma_{rough}}$$
(2)

Therefore  $Flux_{wire}$  can be expressed as a function of L and D, which allows for a quantitative calculation of Fluxwire for each single-nanowire device. For a representative device (Fig. 4a), I reaches a plateau of -43 pA when cathodic bias is applied. Correspondingly, J and Flux<sub>geo</sub> are -22 mA/cm<sup>2</sup> and 1,350 electrons/ (nm<sup>2</sup>·s), respectively (-1 mA/cm<sup>2</sup> = 62 electrons/ (nm<sup>2</sup>·s)). When normalizing to the nanowire's actual surface area, the corresponding  $Flux_{wire}$  is dramatically reduced to 13 electrons/ (nm<sup>2</sup>·s), because of the large  $\gamma_{rough}$ . Compared to the photo-generated electron flux of a planar  $n^+p$ -Si electrode (1,240 electrons/ (nm<sup>2</sup>·s) at 0V vs. RHE, see Supplementary Fig. 10), Flux<sub>wire</sub> is diluted by about 100 times. The trend of such a reduced electron flux is elucidated when values of saturated Fluxwire for individual nanowires were plotted against their L and D (Fig. 4b). Here we take advantage of the fact that the dimensions of each single nanowire are not only highly tunable but also can be reliably measured, in contrast to the inhomogeneity that typically occurs for ensemble devices. Ranging from 30 to 7 electrons/ (nm<sup>2</sup>·s),  $Flux_{wire}$  follows a generally decreasing trend as L becomes longer or D becomes smaller (Supplementary Fig. 11). Such dependence can be clearly seen when  $Flux_{wire}$  is correlated with  $\gamma_{rough}$ , which incorporates the impact of both L and D (Fig. 4c). Flux<sub>wire</sub> tends to decrease as  $\gamma_{rough}$  increases. The effective reduction of electron flux on the nanowire surface can be estimated by considering the light absorption within a cylindrical silicon absorber, and is found to scale with the  $\gamma_{rough}$  of the individual nanowires (Supplementary Fig. 13).

The characterization of  $Flux_{wire}$  provides quantitative insight into the nanowire geometry's benefits in photoelectrochemistry. In principle, the loaded electrocatalyst should have a sufficiently high TOF to handle the photo-generated electron flux<sup>11</sup>. As a result, the much reduced  $Flux_{wire}$  (7-30 electrons/ (nm<sup>2</sup>·s) under 1 Sun illumination measured in this study, compared to typical ~1,200 electrons/ (nm<sup>2</sup>·s) for a planar photoelectrode) can significantly alleviate the requirement on the TOFs of loaded electrocatalysts and consequently reduce the necessary overpotential as compared with a planar counterpart (see Supplementary Table 2 for specific values). This is especially critical for more complicated and sluggish electrochemical reactions such as CO<sub>2</sub> reduction<sup>26, 27</sup>, where the electrocatalyst typically needs a large overpotential to reach an appreciable TOF<sup>28-30</sup>. In addition, the systematic trend of  $Flux_{wire}$  introduces the possibility to design specific nanowire geometries to match the activities of different loaded electrocatalysts in different PEC reactions. This single-nanowire photoelectrode represents a model system that can be used to study and design nanowire photoelectrodes for next-generation solar-to-fuel conversion devices.

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#### **Author contributions**

Y. S., C. L. and P. Y. conceived and designed the experiments. Y. S., C. L., S. B. and J. T. fabricated the single-nanowire devices. Y. S. and C. L. performed the PEC measurements on single-nanowire devices. Y. S., C. L. and A. F. carried out the numerical calculation. Y. S. and Q. K. fabricated and characterized the nanowire array samples. N. K. carried out the high-resolution TEM imaging. Y. S., C. L. and P. Y. co-wrote the paper. All authors discussed the results and revised the manuscript.

### **Additional information**

The authors declare no competing financial interests. Supplementary information accompanies this paper at <u>www.nature.com/naturenanotechnology</u>. Reprints and permission information is available online at <u>http://www.nature.com/reprints</u>. Correspondence and requests for materials should be addressed to P. Y.

#### **Figure Captions**

Figure 1. Single-nanowire photoelectrode for PEC measurements. a, Schematics of the single Si nanowire for the PEC process. Under illumination, the photo-excited electron-hole pairs are produced and subsequently separated at the nanowire/electrolyte interface because of the band bending. The electrons then move to the Pt catalytic sites and carry out the proton reduction. b, SEM image of the individually addressable single nanowires. The Si layer of the SOI substrate is patterned into nine electrically isolated, oxide-passivated electrodes, with an oxide layer underneath. The single Si nanowires are vertically grown on these isolated Si electrodes by the vapor-liquid-solid (VLS) mechanism<sup>23</sup>. The scale bar is 10  $\mu$ m.

Figure 2. Schematic illustrations of the fabrication and measurement processes. a, Outline of the post-growth fabrication process (see Methods and Supplementary Fig. 1 for details). Devices with two kinds of doping profiles (p-Si and  $n^+p$ -Si) were fabricated for comparison. b, The PEC measurement scheme. A two-electrode configuration was used to characterize the I-V properties of single nanowires. While the Si nanowire serves as the working electrode, a Pt wire functions as the counter/reference electrode whose electrochemical potential was calibrated (Supplementary Fig. 4). The reactor volume in which the PEC processes occur is defined by a polydimethylsiloxane (PDMS) chamber. A probe makes electrical contact to each nanowire through the outside pads, while the chamber is illuminated from above.

**Figure 3. PEC performance of the single-Si-nanowire devices. a**, *I-V* characteristics of singlenanowire devices. The measurement was carried out in 0.1 M K<sub>2</sub>SO<sub>4</sub> solution adjusted to pH ~ 2 with H<sub>2</sub>SO<sub>4</sub>. Under simulated sunlight (100 mW/cm<sup>2</sup>, AM 1.5G), both the *p*-Si device ( $L = 8 \mu m, D = 620 nm$ ) and  $n^+p$ -Si device ( $L = 12.5 \mu m, D = 530 nm$ ) have significant photoresponses. The purple arrows indicate the onsets of photocurrent as defined in **c**. **b**, Repeated scans of the  $n^+p$ -Si device displayed in **a**. **c**, The statistical distribution of onset potentials for seven *p*-Si and nine  $n^+p$ -Si devices. To evaluate the photovoltage response of the single-nanowire devices, the onset potential is defined as the potential *vs*. RHE where  $\Delta I$  is -0.5 pA. Here  $\Delta I$  is the difference between the photocurrent and the dark current. The pink band shows the difference in the average onset potential between *p*-Si and  $n^+p$ -Si devices.

Figure 4. Analysis of the flux of photo-generated electrons. a, The PEC behavior of a representative  $n^+p$ -Si device ( $L = 13 \ \mu m, D = 490 \ nm$ ). The four y-axes represent (from left to right) the recorded photocurrent (I), the current density based on the geometric cross-sectional area (J), the electron flux normalized to the geometric cross-sectional area (Flux<sub>geo</sub>), and the electron flux through the nanowire's entire surface (Flux<sub>wire</sub>), respectively. **b**, The statistical distribution of saturated Flux<sub>wire</sub> as a function of L and D of individual nanowires. Each data point represents a repeatable measurement of one single-nanowire device. **c**, The dependence of saturated Flux<sub>wire</sub> on the roughness factor of individual nanowires ( $\gamma_{rough}$ ).

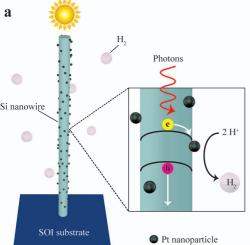
### Methods

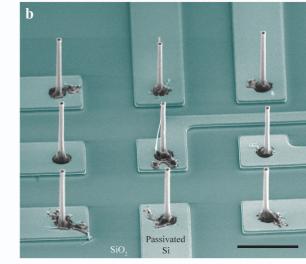
**Growth of Si nanowires.** The heavily doped ( $\rho$  of 0.01-0.05  $\Omega$  cm) *p*-type (boron) SOI wafers with 3 µm device layer oriented <111> and 2 µm buried oxide layer were obtained from WRS Materials. The device layer was first thinned down to 1.5 µm by thermal oxidation and subsequent etching in buffered hydrofluoric acid (BHF). Then the device layer was further doped with boron (Techneglas GS-139) at 1,050 °C for 10 hours, followed by a second thermal oxidation and BHF etching. The resulting device layer was ~1 µm thick with a resistivity < 0.002  $\Omega$  cm. The Si electrodes were patterned by photolithography and anisotropic plasma etching (Surface Technology Systems), and then thermally oxidized to form a 300 nm thick oxide. The bonding pads were defined by photolithography and anisotropic plasma etching of the oxide (Plasma-Therm PK-12 RIE). The catalysts for VLS growth were defined by photolithography, anisotropic plasma etching of the oxide, and subsequent electron-beam evaporation of gold (150 nm). The isolated Si nanowires were grown at 875 °C for 10-15 minutes with SiCl<sub>4</sub> as the precursor and 10% hydrogen in argon as the reducing agent.

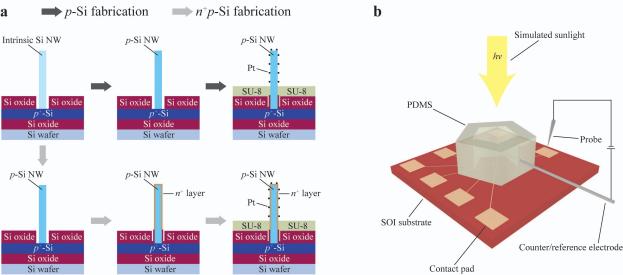
Device fabrication after growth. The as-grown isolated Si nanowires were etched in BHF for 30 seconds and subsequently soaked in gold etchant (Transene) for 30 minutes. Then the nanowires were thermally oxidized at 1,000 °C for 1 hour, followed by etching in BHF. The boron doping process was split into two parts. First, boron was pre-deposited at the nanowire surface at 750 °C for 1 hour, with 1% BCl<sub>3</sub> in argon as the precursor and 10% hydrogen in argon as the reducing agent. Second, the boron atoms at the nanowire surface were driven into the nanowire at 1,000 °C for 5 hours in vacuum. The resulting boron doping level of the single nanowires was estimated to be  $\sim 2 \times 10^{17}$ /cm<sup>3</sup>. Such estimation is based on the resistivity of the SOI control chip, which was approximated by four-probe measurement. The key steps used in the  $n^+$  layer fabrication are given below (see Supplementary information for details). First, the p-Si nanowires were thermally oxidized at 1,000 °C for 1 hour, then coated with  $\sim 1 \mu m$  of I-line photoresist at the base of the nanowires. Second, BHF was used to etch the oxide on the nanowire upper exposed part, followed by I-line removal in acetone. Third, a Si handle wafer was spin-coated with arseniccontaining spin-on dopant (SOD) (Filmtronics, Inc.) and baked at 150 °C for 30 minutes. Then the device chip was placed on the SOD coated Si wafer, and annealed at 900 °C for 4 minutes in an N<sub>2</sub> atmosphere to form an  $n^+$  layer at the nanowire's surface. Fourth, SU-8 dissolved in ethyl acetate was drop-cast onto the device chip, resulting in a  $\sim$ 3 µm thick SU-8 layer at the base of the device chip. With the SU-8 at the bonding pad scratched to expose the electrode's surface, the chip was baked in order to harden the SU-8. Finally, after a quick etching in BHF, the device chip was soaked in the solution containing 0.1 M HF and 0.2 mM K<sub>2</sub>PtCl<sub>6</sub> for 3 minutes to carry out the platinum deposition on the nanowire surface<sup>22</sup>.

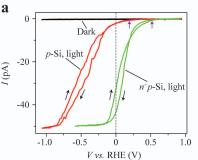
**PEC measurement.** A 150 W Xenon arc lamp (Newport Corporation) with an AM1.5G filter was used to characterize the PEC response of the single-nanowire devices. As a top-illumination measurement, the angle

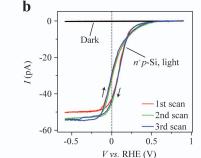
between the incident light and the axis of the single nanowire is smaller than 3°. The light intensity was calibrated using a Si photodiode referenced to an NREL calibrated Si photodiode. All PEC measurements were carried out in a two-electrode configuration. A platinum wire worked as the counter electrode, whose electrochemical potential was immediately calibrated with Ag/AgCl (0.1 M KCl) after the PEC measurement (Supplementary Fig. 4). A PDMS chamber was used to define the reactor space, where the nanowire device was immersed in 0.1 M aq. K<sub>2</sub>SO<sub>4</sub> adjusted to pH  $\sim$  2 using H<sub>2</sub>SO<sub>4</sub>. *I-V* characterization was performed with a Keithley 2636 source-measure unit (SMU), and the typical potential sweep rate was 10 mV/s. The open-circuit instrumental noise current level is less than 0.5 pA.

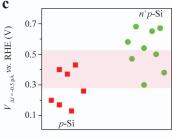


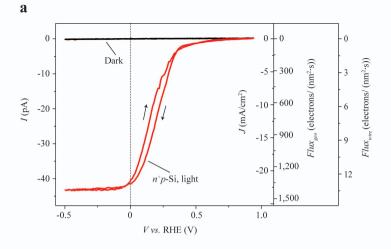


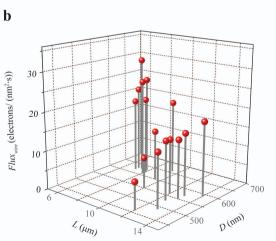












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